ABSTRACT OF THE DISCLOSURE

A data storage portion stores a measurement value of registration accuracy after photolithography process and a measurement value of registration accuracy after etching measured by a registration inspection apparatus. An operation portion calculates an amount of correction for the registration inspection apparatus by subtracting the measurement value of registration accuracy after etching from the measurement value of registration accuracy after photolithography process stored in data storage portion. A measurement correction portion instructs an amount of correction calculated by the operation portion to registration inspection apparatus. Therefore, even if an underlying layer is displaced through the photolithography process, the registration inspection apparatus can be controlled so as to enhance process accuracy in terms of attaining a target value.